## **ABSTRACT**

An aqueous polishing composition comprises a corrosion inhibitor for limiting removal of an interconnect metal with an acidic pH. The composition includes an organic-containing ammonium salt formed with

$$R_1$$
 $R_4 - N^+ - R_2$ 
 $R_3$ 

 $R_1$ ,  $R_2$ ,  $R_3$  and  $R_4$  are radicals,  $R_1$  has a carbon chain length of 2 to 15 carbon atoms. The organic-containing ammonium salt has a concentration that accelerates TEOS removal and decreases removal of at least one coating selected from the group consisting of SiC, SiCN,  $Si_3N_4$  and SiCO.

Attorney Docket No.: 02024US